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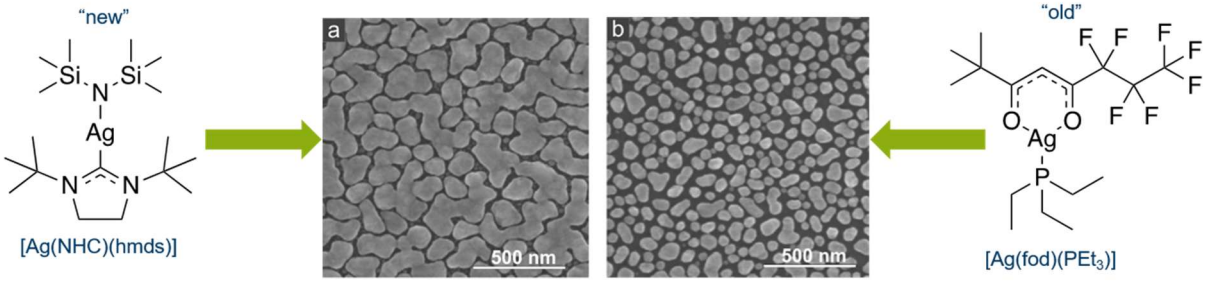

Figure 1. Comparison of the APP-ALD processes established with the two precursors [Ag(NHC)(hmds)] and [Ag(NHC)(fod)] under nominally identical process conditions (T_{dep} = 100 °C, 1200 cycles). The "new" precursor delivers a higher growth rate and the layers feature a reduced onset of percolation. Adapted from Boysen et al.[1]. © 2018 Wiley-VCH Verlag GmbH & Co. KGaA, Weinheim.

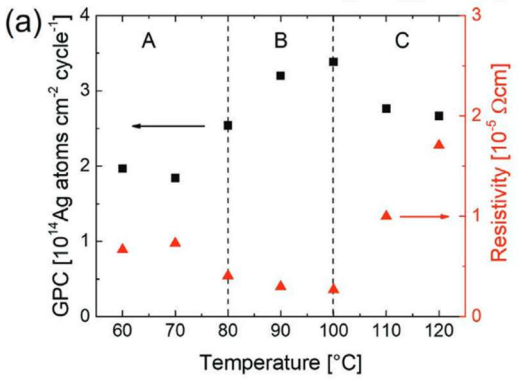

Figure 2. Low deposition temperatures (min. 60 °C) achieved with the precursor [Ag(NHC)(hmds)] in APP-ALD. Adapted from Hasselmann et al.[3] under the CC-BY license (https://creativecommons.org/licenses/by/4.0/).

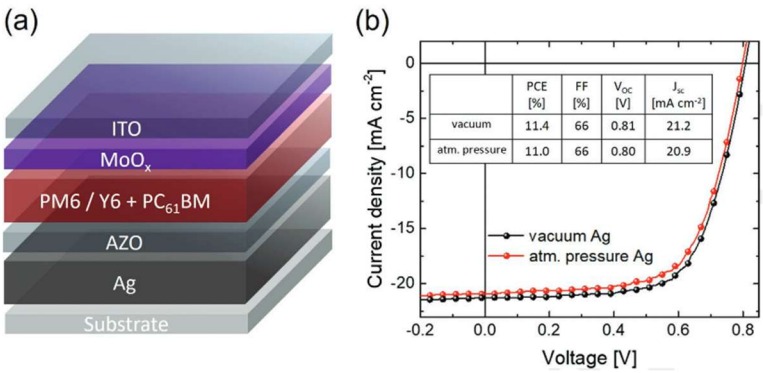

Figure 3. Silver deposited by APP-ALD with [Ag(NHC)(hmds)] and H_2/Ar plasma as the bottom electrode in organic solar cells. a) Schematic of the cell-stack. b) Device characteristics compared to PVD silver films. Adapted from Hasselmann et al.[3] under the CC-BY license (https://creativecommons.org/licenses/by/4.0/).